

<p style="text-align: center;">INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</p> <p style="text-align: right;">O I P E U S A P A T E N T & T R A D E M A R K O F F I C E D E C 1 8 2003</p>		ATTY. DOCKET NO. 005918 USA/FPS/MMCS/APC		SERIAL NO. 09/943,955		
		RECEIVED Technology Center 2100		DEC 19 2003		
				APPLICANT SHANMUGASUNDRAM et al.		
				FILING DATE August 31, 2001	GROUP 2122	
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
L.J.M-E	4,207,520	06/10/80	Flora et al.	324	238	04/06/78
L.J.M-E	4,209,744	06/24/80	Gerasimov et al.	324	241	03/27/78
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L.J.M-E	6,041,263	03/21/00	Boston et al.	700	32	10/01/97
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L.J.M-E	6,271,670	08/07/01	Caffey	324	642	02/08/99
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FOREIGN PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation
						Yes
L.J.M-E	WO 01/11679	02/15/01	WIPO	—	—	X
L.J.M-E	WO 01/080306	10/25/01	WIPO	—	—	X
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
L.J.M-E	Miller, G. L., D. A. H. Robinson, and J. D. Wiley. July 1976. "Contactless measurement of semiconductor conductivity by radio frequency-free-carrier power absorption." <i>Rev. Sci. Instrum.</i> , Volume 47, No. 7. pp. 799 – 805.					
L.J.M-E	1999. "Contactless Bulk Resistivity/Sheet Resistance Measurement and Mapping Systems." www.Leighton.com/fabtech1/index.html .					
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EXAMINER	DATE CONSIDERED					
Lynette J. Umz-Eromini	5/2/2004					

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation
						Yes
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
<i>L.J.M-E.</i>	El Chemali, Chadi et al. July/August 2000. "Multizone uniformity control of a chemical mechanical polishing process utilizing a pre- and postmeasurement strategy." <i>J. Vac. Sci. Technol.</i> Volume 18, No. 4. pp. 1287 – 1296.					
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<i>L.J.M-E.</i>	08 August 2003. PCT International Search Report from PCT/US03/08513.					
<i>L.J.M-E.</i>	14 October 2003. PCT International Search Report from PCT/US02/21942.					
<i>L.J.M-E.</i>	20 October 2003. PCT International Search Report from PCT/US02/19116.					
<i>L.J.M-E.</i>	23 October 2003. PCT International Preliminary Examination Report from PCT/US01/24910.					
<i>L.J.M-E.</i>	"NanoMapper wafer nanotopography measurement by ADE Phase Shift." http://www.phase-shift.com/nanomap.shtml .					
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<i>L.J.M-E.</i>	"NanoMapper FA factory automation wafer nanotopography measurement." http://www.phase-shift.com/nanomapperfa.shtml .					
EXAMINER	DATE CONSIDERED					
<i>Dynette J. Umeg-Eunini</i>	<i>5/2/2004</i>					

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